

<b>Notice of References Cited</b>	Application/Control No. 10/784,608	Applicant(s)/Patent Under Reexamination DESIMONE ET AL.	
	Examiner Irina S. Zemel	Art Unit 1711	Page 1 of 1


**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2003/0006477 A1	01-2003	Gallahger et al.	257/527
	B	US-6,187,248	02-2001	O'Neill et al.	264/425
	C	US-			
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	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Low Dielectric Constant Materials for Advanced Microelectronics, IBM Research, 2-2002
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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